	Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-893001	Application No. 10/789,670
Information Disclosure Statement by Applicant		Applicant Arun Ramamoorthy et al.		
ı	(Use several sheets if necessary)		Filing Date	Group Art Unit
ı	(37 CFR §1.98(b))		February 27, 2004	1724

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
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Foreign Patent Documents or Published Foreign Patent Applications								
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Initial	ID	Number	Date	Patent Office	Class	Subclass	Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							

Other Documents (include Author, Title, Date, and Place of Publication)						
Examiner	Desig.					
Initial	ID D	Document				
	AQ	Chauhan, M.M., et al., "Photoresist Outgassing in EUV", 2000 March Meeting: Bulletin of the American Physical Society, 45(1):563, abstract #L36.112, March 2000.				
	AR	Moors, R., et al., "Electrostatic mask protection for extreme ultraviolet lithography", Journal of Vacuum Science & Technology B: Microelectronics and Nanometer Structures, 20(1):316-320, Jan/Feb 2002.				
	AS					
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